

Detailed Action

Allowable subject matter

The following is an examiner's statement of the reasons for allowance:

The prior art does not teach or suggest a longitudinal type of thermal processing apparatus comprising: a processing container made of quartz, having an opening part at a lower end thereof, a lid provided under the opening part, capable of moving up and down wherein the lid has an inner lid part made of quartz that comes in contact with a lower-end surface of the opening part, and an outer lid part made of a metal that covers an outside surface of the inner lid part, the lower-end surface of the opening part and an upper-end surface of the inner lid part, which come in contact with each other, are mirror-finished, a first flange is provided at an outside periphery of the opening part, the first flange is located higher than the lower-end surface of the opening part, a second flange is provided at an outside periphery of the inner lid part, the second flange is located lower than the upper-end surface of the inner lid part, a flange holder is provided between the first flange and the second flange, and a channel for vacuuming is formed by: an inner surface of the flange holder, a lower surface of the first flange, an upper surface of the second flange, an outer surface of the inner lid part from the second flange to the upper-end surface, and an outer surface of the opening part from the lower-end surface to the first flange.

One of the references used was a Kenichi's reference (JP 07-029841). However, Kenichi or any other reference used in the rejection of claim 4 does not disclose: a first flange is provided at an outside periphery of the opening part, the first flange is located

higher than the lower-end surface of the opening part, a second flange is provided at an outside periphery of the inner lid part, the second flange is located lower than the upper-end surface of the inner lid part, a flange holder is provided between the first flange and the second flange, and a channel for vacuuming is formed by: an inner surface of the flange holder, a lower surface of the first flange, an upper surface of the second flange, an outer surface of the inner lid part from the second flange to the upper-end surface, and an outer surface of the opening part from the lower-end surface to the first flange.

Withdrawn claims 5, 6, 7 and 9 are also allowed and therefore are rejoined with the claim 4 above.

Any comments considered necessary by the applicant must be submitted no later than the payment of the issue fee and to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to SATISH CHANDRA whose telephone number is (571)272-3769. The examiner can normally be reached on 8 a.m. - 4:30 p.m..

If attempts to reach the examiner by telephone are unsuccessful, Primary Examiner, Jeffrie R. Lund can be reached on 571-272-1437. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Satish Chandra/
Examiner, Art Unit 1792

/Jeffrie R. Lund/
Primary Examiner, Art Unit 1792